

0160-0193-0 PCT



#8(B)
10/31/01

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

HIROSHI IKEDA ET AL

: EXAMINER: VANOVY, T.

SERIAL NO: 09/463,961

:

FILED: MAY 25, 2000

: GROUP ART UNIT: 1754

FOR: METHOD AND APPARATUS
FOR PROCESSING EXHAUST
GAS OF SEMICONDUCTOR
FABRICATION

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

RECEIVED
OCT 03 2001
TC 1700

SIR:

In response to the Office Action dated June 19, 2001, the period for response having been extended to October 19, 2001, by a petition for extension of time filed herewith, please amend the application identified above as follows (marked-up copy of amendments attached):

IN THE TITLE

Please replace the title with the following title:

--PROCESS AND APPARATUS FOR TREATING SEMICONDUCTOR

PRODUCTION EXHAUST GASES--

IN THE SPECIFICATION

Page 1, after the title, please insert the continuing data:

--This application is a 371 of PCT/JP98/04666 filed October 15, 1998.--

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simply 10000